

CHEMICALLY AMPLIFIED RESIST MATERIAL AND PATTERNING  
METHOD USING SAME

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ABSTRACT OF THE DISCLOSURE

10       A chemically amplified resist material comprising a  
base resin and a photo acid generator having sensitivity  
at the wavelength of patterning exposure; wherein, the  
chemically amplified resist material further comprising  
an activator that generates an acid or a radical by a  
treatment other than the patterning exposure. A  
15       patterning method using the same is also disclosed.